

經濟部智慧財產局專利申請案核駁理由先行通知

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發文日期：中華民國九十二年十月九日
發文文號：（八九二）智專二（二）〇二〇三字第〇九二二二〇二〇五〇號

主旨：第〇九〇一〇四三八七號專利申請案經審查後發現尚有如說明三所述不明確之處，台端（貴公司）若有具體反證資料或說明，請於文到次日起六十日內提出申復說明及有關反證資料一式二份。若屆期未依通知內容辦理者，專利專責機關得依現有資料續行審查，請查照。

說明：

- 一、本案如有修正應依專利法第四十四條、第四十四條之一、第一百零二條之一、專利法施行細則第二十八條及本局九十一年十一月八日智法字第〇九一八六〇〇一一八—〇號公告之規定辦理並繳修正規費新台幣一千元正（如有補充、修正說明書或圖式者，應備具補充、修正申請書一式二份，並檢送補充、修正部份劃線之說明書或圖式修正頁一式二份及補充、修正後無劃線之說明書或圖式替換頁一式三份；如補充、修正後致原說明書或圖式頁數不連續者，應檢附補充、修正後之全份說明書或圖式一式三份至局）。
- 二、若希望來局當面示範或說明，請於申復說明書內註明「申請面詢」，本局認為有必要時，另安排地點、時間舉辦「面詢」，並繳交規費新台幣二千元正。
- 三、本案經審查認為：

（一）本案優先權主張，日本優先權日期為88年5月22日，案號：特願2001-188256號。

第一頁

- （二）本案可提供高傳真度及高孔徑比之電漿顯示器面板及其驅動方法，係多數個第一和第二電極相鄰交替放置，第三電極橫跨第一和二電極形成；在第二和三電極進行位址放電，進行輔助放電減少壁電荷容量，及交替施加持續脈波於第一和二電極，進行持續放電。
- （三）查88年7月1日專利公告編號337333號，申請日為87年5月25日，名稱：電漿顯示板及其驅動方法，係 \times 和 \times 電極交替平行安排，和橫跨 \times 和 \times 電極之 Δ 電極形成，依第5圖方式分別施加電極驅動訊號，如申請專利範圍第20項所述，完全抹除壁電荷，再產生定址放電，再週期性施加資料電極。
- （四）本案與引證案具完全相同結構之電漿顯示板，和相同的電極位址和資料驅動方法，本案只是單純將壁電荷減少在第二和三電極進行位址放電時，而引證案在起始步驟時，並且引證案可完全抹除，本案只是減少，本案申請專利之發明，與申請在先而在其申請後始公告之發明專利申請案所附說明書載明之內容相同。
- （五）又本案申請專利範圍有下列錯誤，一併指明：第一、7、17項之標的不明確；第20項之標的與依附主項標的不同，依附錯誤。

經濟部智慧財產局

(ENGLISH TRANSLATION)

OFFICIAL LETTER

Date of Receipt: October 14, 2003

FROM: The Intellectual Property Bureau
Ministry of Economic Affairs
TO: Fujitsu Hitachi Plasma Display Limited
C/O: Patrick I. C. Yun/William W. L. Chen, patent attorney

SUBJECT

The rejection of patent application no. 90104387 has been tentatively concluded. Before any formal issuance of a first Office Action, the applicant is invited to submit, in duplicate, any rebuttal evidence and clarification (along with any amendment) within sixty (60) days of the day following the date of receipt of this Official Letter. **The deadline cannot be extended.** Failure to comply with the requirement, or a late reply to this Letter, will result in the rejection of this application.

CONTENTS

(Translator's note: This first paragraph is not translated herein as it only relates to the formality requirements in any documents to be submitted.)

If the applicant wishes to have a personal interview or demonstration with the Examiner, a request may be made in the Response. If deemed necessary, the time and place for holding the interview will be arranged.

The Examiner is of the opinion that:

1. This application claims priority based on Japanese Application 2001-188256, and the priority date is June 22, 2000.
2. This invention is aimed at providing a plasma display panel with high definition and high aperture ratio, as well as method of driving the same. The plasma display panel includes a plurality of first and second electrodes which are disposed adjacently and alternately, and third electrodes formed across the first and second electrodes. The method comprises the steps of: carrying out an address discharge between said second electrodes and said third electrodes; carrying out auxiliary discharge to decrease the volume of wall charges; and carrying out a sustain discharge by alternately applying sustain pulses to the first and second electrodes.
3. Taiwan Publication No. 397963 is filed on May 25, 1997 and is entitled "Plasma Display Panel and Driving Method." The publication discloses that X and Y electrodes are arranged alternately, and that electrodes A are formed across X and Y electrodes. Driving signals are impressed to the electrodes as shown in Figure 5. As recited in claim (20), wall charges are erased completely, an address discharge is generated, and data electrodes are impressed sequentially.
4. This application discloses a plasma display panel with a structure which is totally the same as that of the cited reference, and a similar method of driving address and data electrodes. The present invention reduces the volume of the wall charge only when an address discharge is carried out at the first and third electrodes, whereas the wall charge can be erased completely at the stage of initialization. The present invention only makes a reduction of wall charge. This application was filed for an Invention Patent. The contents in the application are similar to that of the specification of the cited invention patent application which was filed prior to this application but published later than the filing of this application.